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Authors: Danno, K; Nakamura, D; Kimoto, T

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Investigation of carrier lifetime in 4H-SiC epilayers and lifetime control by electron irradiation

Katsunori Danno  
Department of Electronic Science and Engineering, Kyoto University, Kyoto 615-8510, Japan

Daisuke Nakamura  
Department of Electronic Science and Engineering, Kyoto University, Kyotodaigaku-Katsura, Nishikyko, Kyoto 615-8510, Japan and Toyota Central R&D Laboratories, Inc, Aichi 480-1192, Japan

Tsunenobu Kimoto  
Department of Electronic Science and Engineering, Kyoto University, Nishikyo, 615-8510, Japan  

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Carrier lifetimes in 4H-SiC epilayers are investigated by differential microwave photoconductivity decay measurements. When the $Z_{1/2}$ concentration is higher than $10^{13}$ cm$^{-3}$, the $Z_{1/2}$ center works as a recombination center. In this case, carrier lifetimes show positive dependence on the injection level (number of irradiated photons). On the other hand, other recombination processes such as surface recombination limit the lifetime when the $Z_{1/2}$ concentration is lower than $10^{13}$ cm$^{-3}$. In this case, carrier lifetimes have decreased by increasing the injection level. By controlling the $Z_{1/2}$ concentration by low-energy electron irradiation, the lifetime control has been achieved. © 2007 American Institute of Physics. [DOI: 10.1063/1.2740580]

Silicon carbide (SiC) is an attractive material for developing high-power, high-temperature, and high-frequency devices, owing to its superior properties. To realize SiC power devices with a high blocking voltage more than several kilovolts, bipolar devices such as $p-i-n$ diodes, thyristors, and insulated gate bipolar transistors possess a great promise in terms of lower on resistance owing to the effect of conductivity modulation. A long carrier lifetime is required for effective conductivity modulation. Although the lifetime of SiC epilayers has been investigated by several groups, it does not exceed 1–2 $\mu$s, which is a few orders of magnitude shorter than that of high-purity silicon. Too long lifetimes, on the other hand, will cause considerably large reverse recovery, leading to limited switching frequency and excessive switching loss. Therefore, carrier lifetimes should be controlled to achieve an optimum lifetime value and its profile.

In this work, carrier lifetimes in 4H-SiC are investigated by differential microwave photoconductivity decay ($\mu$-PCD) measurements. In particular, impacts of deep levels on carrier lifetimes are studied. From the results, control of carrier lifetimes is demonstrated by low-energy electron irradiation.

Epitaxial layers were grown on 8° off-axis 4H-SiC(0001) $n^+$ substrates by horizontal hot-wall chemical vapor deposition in a SiH$_4$–C$_3$H$_8$–H$_2$ system. Substrates purchased from Cree or prepared at Toyota Central R&D Labs., Inc. were used in this study. Epitaxial growth was performed at 1650 °C with a typical reactor pressure of 80 Torr. The C/Si ratio was varied from 0.8 to 1.3 by changing C$_3$H$_8$ flow rate at a fixed SiH$_4$ flow rate All the epilayers were intentionally doped with nitrogen to the $10^{15}$ cm$^{-3}$ range. Typical growth rate was 10–15 $\mu$m/h, and thickness of the epilayers was approximately 50 $\mu$m.

Carrier lifetimes of as-grown and electron-irradiated 4H-SiC epilayers were investigated by differential $\mu$-PCD measurements. An yttrium aluminum garnet third harmonic generation laser ($\lambda$=355 nm) was used as an excitation source. The typical number of photons irradiated onto the sample surface per unit area was $2 \times 10^{14}$ or $1 \times 10^{15}$ cm$^{-2}$, which leads to a high injection level of low $10^{16}$–low $10^{17}$ cm$^{-3}$. Electron irradiation was performed at an energy of 160 keV without intentional sample heating to introduce deep levels. Concentration of deep levels was evaluated by deep level transient spectroscopy (DLTS).

Figure 1 shows the photoconductivity decay curves measured for 4H-SiC epilayers grown with a C/Si ratio of 0.9 or 1.1, respectively. The illumination intensity for the measurement is from 1/2 concentration is 1.3 $\times 10^{15}$ cm$^{-3}$ for the sample grown at a C/Si ratio of 0.9, and 4.4 $\times 10^{15}$ cm$^{-3}$ for the sample grown at a C/Si ratio of 1.1, respectively. The illumination intensity for the measurement is from $2 \times 10^{15}$ to $1 \times 10^{17}$ cm$^{-2}$.

FIG. 1. Photoconductivity decay curves measured for 50-$\mu$m-thick 4H-SiC(0001) epilayers grown at a C/Si ratio of (a) 0.9 and (b) 1.1. The net donor concentration is (1.2–1.5) $\times 10^{15}$ cm$^{-3}$ for both samples. Trap ($Z_{1/2}$ center) concentration is 1.3 $\times 10^{15}$ cm$^{-3}$ for the sample grown at a C/Si ratio of 0.9, and 4.4 $\times 10^{15}$ cm$^{-3}$ for the sample grown at a C/Si ratio of 1.1, respectively. The illumination intensity for the measurement is from $2 \times 10^{15}$ to $1 \times 10^{17}$ cm$^{-2}$.

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$^a$Electronic mail: kimoto@kuee.kyoto-u.ac.jp
1. The illumination intensity (number of irradiated photons per unit area: \(N_0\)) is from \(2 \times 10^{13}\) to \(1 \times 10^{15}\) cm\(^{-2}\). The net donor concentration estimated from capacitance-voltage measurement (1.2–1.5)\(\times 10^{15}\) cm\(^{-3}\) for the samples. The \(Z_{1/2}\) center (\(E_C\)−0.65 eV) (Ref. 10) and \(EH_{6/7}\) center (\(E_C\)–1.55 eV) (Ref. 11) were dominant deep levels in the as-grown n-type 4H-SiC epilayers, and their concentrations were \(1.3 \times 10^{13}\) cm\(^{-3}\) (\(Z_{1/2}\)) and \(1.2 \times 10^{15}\) cm\(^{-3}\) (\(EH_{6/7}\)) for the sample grown at a C/Si ratio of 0.9, and \(4.4 \times 10^{12}\) cm\(^{-3}\) (\(Z_{1/2}\)) and \(3.6 \times 10^{12}\) cm\(^{-3}\) (\(EH_{6/7}\)) for the sample grown at a C/Si ratio of 1.1, respectively. A relatively long carrier lifetime of 2.3 \(\mu\)s could be obtained for the sample grown at a C/Si ratio of 1.1, probably because of low trap concentration of the sample. As shown in Fig. 1, the injection-level dependence of the lifetime is different between the samples: The carrier lifetime increased by increasing the injection level in the sample grown at a C/Si ratio of 0.9 and decreased in the sample grown at a C/Si ratio of 1.1. The result indicates that different types of lifetime killers affect carrier lifetimes for the different samples.

Figure 2 shows the relation between the lifetime of the carrier lifetime measured with an illumination intensity of \(2 \times 10^{14}\) cm\(^{-2}\) and the \(Z_{1/2}\) concentration (the \(EH_{6/7}\) concentration was always close to the \(Z_{1/2}\) concentration). After the lifetime mapping and DLTS mapping measurements on four different samples, the \(Z_{1/2}\) concentration and carrier lifetime at identical locations were plotted in the figure. When the \(Z_{1/2}\) concentration is higher than \((1–2) \times 10^{13}\) cm\(^{-3}\), the inverse of carrier lifetime is proportional to the \(Z_{1/2}\) concentration. However, the correlation between the lifetime and the \(Z_{1/2}\) concentration is not clear when the \(Z_{1/2}\) concentration is in the \(10^{12}\) cm\(^{-3}\) range. In general, a carrier lifetime \(\tau\) is given by

\[
\frac{1}{\tau} = \frac{1}{\tau_{SRH}} + \frac{1}{\tau_{other}},
\]

where \(\tau_{SRH}\) is the Shockley-Read-Hall (SRH) lifetime governed by a recombination center,\(^{12,13}\) and \(\tau_{other}\) is the carrier lifetime governed by other processes such as surface recombination. In Fig. 2, \(\tau_{other}\) is constant irrespective of the \(Z_{1/2}\) concentration. According to the SRH model, when the injection level is much higher than the steady-state carrier concentration (high injection level), the inverse of SRH lifetime \((1/\tau_{SRH})\) is given by

\[
\frac{1}{\tau_{SRH}} = \frac{\sigma_p v_{th,p} \sigma_n v_{th,n}}{\sigma_p v_{th,p} + \sigma_n v_{th,n}} N_T = a N_T,
\]

where \(\sigma_p\) and \(\sigma_n\) are the capture cross section of the recombination center for holes and electrons, \(v_{th,p}\) and \(v_{th,n}\) are the thermal velocities of holes and electrons, \(N_T\) is the concentration of the recombination center, and \(a\) is the constant. Based on this model expressed by Eq. (1), the experimental data were fitted, where the \(\tau_{other}\) and \(a\) are the fitting parameters. The fitted result is shown by a solid line for \(1/\tau_{SRH} + 1/\tau_{other}\), and two broken lines for \(\tau_{SRH}\) and \(\tau_{other}\), respectively. As shown in the figure, the inverse of carrier lifetimes \((\tau)\) is proportional to the \(Z_{1/2}\) concentration when the concentration is higher than \((1–2) \times 10^{13}\) cm\(^{-3}\). Therefore, the \(Z_{1/2}\) center (or \(EH_{6/7}\) center) works as an effective recombination center. On the other hand, the inverse of carrier lifetime is almost constant irrespective of the \(Z_{1/2}\) concentration when the \(Z_{1/2}\) concentration is lower than \((1–2) \times 10^{13}\) cm\(^{-3}\). In this case, the inverse of SRH lifetime is very small because the trap concentration is low, and the carrier lifetime may be governed by other recombination processes.

The inverse of the carrier lifetime is proportional to the \(Z_{1/2}\) concentration when the trap concentration is high enough. Since the \(Z_{1/2}\) concentration can be selectively increased by low-energy electron irradiation,\(^{15,16}\) the lifetime control has been attempted. The starting material was a 50-\(\mu\)m-thick 4H-SiC epilayer doped to \(1.5 \times 10^{15}\) cm\(^{-3}\), the \(Z_{1/2}\) concentration in which is \(2 \times 10^{13}\) cm\(^{-3}\). Electron irradiation was performed with the fluence range from \(2 \times 10^{16}\) to \(1 \times 10^{18}\) cm\(^{-2}\), and subsequent annealing was performed at 950 or 1550 °C for 30 min. In 160 keV electron-irradiated samples annealed at 950 °C, the \(Z_{1/2}\) and \(EH_{6/7}\) concentrations are predominantly increased in the upper half of band gap of 4H-SiC.\(^{16}\) In the lower half of band gap several kinds of hole traps are also observed after electron irradiation at 160 keV and subsequent annealing at 950 °C, while all the traps except for the D center\(^{17}\) are annealed out at 1550 °C.\(^{18}\) Note that the annealing at 1550 °C does not influence the \(Z_{1/2}\) and \(EH_{6/7}\) concentrations very much.

The map for fluence of the electron irradiation and the distribution of the \(Z_{1/2}\) concentration in the irradiated epilayer is schematically illustrated in Fig. 3(a). Since selective electron irradiation was performed by using a copper mask, different \(Z_{1/2}\) concentrations ranging from \(1.6 \times 10^{13}\) to \(1.5 \times 10^{15}\) cm\(^{-3}\) for six areas were realized in the sample. In Fig. 3(b), the map of carrier lifetimes of the electron-irradiated sample (annealed at 950 °C for 30 min) for an illumination intensity of \(1 \times 10^{13}\) cm\(^{-2}\) is shown. The carrier lifetime is shorter in the area where the \(Z_{1/2}\) concentration is higher. Moreover, very uniform carrier lifetimes can be realized in each area. These results indicate that the carrier lifetime can be reasonably controlled by electron irradiation.

Figure 4 shows the relation between the inverse of carrier lifetime and the \(Z_{1/2}\) concentration in as-grown and electron-irradiated epilayers, where the lifetimes measured with an illumination intensity of \(2 \times 10^{14}\) and \(1 \times 10^{15}\) cm\(^{-2}\) are presented by open and closed symbols, respectively. In the figure, carrier lifetimes in as-grown (circles) and electron-irradiated samples annealed at 950 °C (triangles) and 1550 °C (squares) are plotted against the \(Z_{1/2}\) concentration. The broken lines denote \(1/\tau_{SRH}\) and \(1/\tau_{other}\) in Eq. (1), and the solid lines represent the sum of them for both illumination intensities.
concentration even when the $Z_{1/2}$ expected from Fig. 4. In such a case, SRH recombination may increasing the illumination intensity when the lifetime is increasing at 1550 °C. Therefore, most hole traps do not seem to be observed after electron irradiation and subsequent annealing at 950 °C, while many of them disappeared after annealing at 1550 °C. Therefore, most hole traps do not seem to work as an effective recombination center.

In previous reports by Tawara et al. and Klein et al., the carrier lifetime showed correlation with the trap ($Z_{1/2}$) concentration even when the $Z_{1/2}$ concentration is lower than $1 \times 10^{13}$ cm$^{-3}$. This difference may be due to difference in the $\tau_{\text{other}}$ value. For example, a lower injection level ($\leq 2 \times 10^{13}$ cm$^{-3}$ in Ref. 8) may lead to longer $\tau_{\text{other}}$, as expected from Fig. 4. In such a case, SRH recombination may be always dominant.

As shown in Fig. 4, the carrier lifetime increases by increasing the illumination intensity when the lifetime is governed by the $Z_{1/2}$ concentration. This result can explain positive dependence of carrier lifetimes on injection level for the epilayer grown at a C/Si ratio of 0.9 [Fig. 1(a)]. Since the $Z_{1/2}$ concentration for the sample is relatively high, 1.3 $\times$ 10$^{13}$ cm$^{-3}$, the $Z_{1/2}$ center worked as effective lifetime killer, and the carrier lifetime shows positive dependence on the injection level. When the recombination via other paths is dominant (the $Z_{1/2}$ concentration is lower than 10$^{13}$ cm$^{-3}$), the lifetime decreases by increasing the illumination intensity, in good agreement with the result shown in Fig. 1(b). A long lifetime under high injection condition is desirable for effective conductivity modulation. On the other hand, a short lifetime under low-injection condition is desirable for reduction of switching loss. Therefore, due to the positive dependence of lifetime on the injection level, introduction of the $Z_{1/2}$ center as a lifetime killer is suitable for control of the carrier lifetime in SiC bipolar power devices.

In summary, carrier lifetimes in 4H-SiC epilayers were investigated by $\mu$-PCD measurements. The $Z_{1/2}$ center works as an effective recombination center when the concentration is higher than low 10$^{13}$ cm$^{-3}$. By controlling the $Z_{1/2}$ concentration by low-energy electron irradiation, control of carrier lifetimes could be realized. When the carrier lifetime is limited by the $Z_{1/2}$ center, the carrier lifetime shows positive dependence on the injection level. On the other hand, other recombination paths than deep levels such as surface recombination might limit carrier lifetimes when the $Z_{1/2}$ concentration is lower than 10$^{13}$ cm$^{-3}$. In this case, the carrier lifetime decreases by increasing the injection level.

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